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INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Applicant

Gabel Chong and Achintya Bhowmik

Filing Date

12/11/01

Group

2874

U.S. PATENT DOCUMENTS

*Examiner Initials	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
KSW	4,420,873	12/20/83	Leonberger et al.	29	576 E	
KSW	4,518,219	5/21/85	Leonberger et al.	350	96.12	
KSW	5,436,991	7/25/95	Sunagawa et al.	385	37	
KSW	5,465,860	11/14/95	Fujimoto et al.	216	24	
KSW	5,540,346	7/30/96	Fujimoto et al.	216	24	
KSW	5,825,047	10/20/98	Ajisawa et al.	257	12	
KSW	5,917,980	6/29/99	Yoshimura et al.	385	129	
KSW	5,943,465	8/24/99	Kawaguchi et al.	385	122	
KSW	6,075,908	6/13/00	Paniccia et al.	385	14	
KSW	6,083,843	7/4/00	Ohja et al.	438	710	
KSW	6,147,366	11/14/00	Drott et al.	257	82	
KSW	6,166,846	12/26/00	Maloney	359	247	
KSW	6,178,281 B1	1/23/01	Sautter et al.	385	129	
KSW	6,195,478 B1	2/27/01	Fouquet	385	17	
KSW	6,215,577 B1	4/10/01	Koehl et al.	359	261	
KSW	6,268,953 B1	7/31/01	Maloney	359	321	
KSW	6,269,199 B1	7/31/01	Maloney	385	14	
KSW	6,304,706 B1	10/16/01	Sugita et al.	385	129	


EXAMINER

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DATE CONSIDERED

5/13/03

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FOREIGN PATENT DOCUMENTS

*Examiner Initials	Document Number	Publication Date	Country	Class	Subclass	Translation	
						Yes	No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

KSW	Farrokh <i>et al.</i> , "High Aspect-Ratio Polysilicon Micromachining Technology," <i>Sensors and Actuators</i> , 87 (March 2000) pp.46-51
KSW	Itoh <i>et al.</i> , "Low-Loss 1.5% Δ Arrayed Waveguide Grating with Spot-Size Converters," <i>NTT Photonics Laboratories</i> , 2 pages
KSW	Mahorowala <i>et al.</i> , "In Situ Measurement of RIE Lag During Polysilicon Etching in a Lam TCP using Full Water Interferometry," (http://www.plasma-processing.com/insitu.htm) (October 22, 2001) pp.1-12
KSW	Moerman <i>et al.</i> , "A Review on Fabrication Technologies for the Monolithic Integration of Tapers with III-V Semiconductor Devices," <i>IEEE Journal of Selected Topics in Quantum Electronics</i> , Vol. 3: No. 6 (December 1997) pp.1308-1320
KSW	Westerheim <i>et al.</i> , "Substrate Bias Effects in High-Aspect-Ratio SiO ₂ Contact Etching Using an Inductively Coupled Plasma Reactor," <i>J. Vac. Sci. Technol.</i> , A 13(3) (May/June 1995) pp.853-858
KSW	Yonemura <i>et al.</i> , "Session FT3-Inductively Coupled Plasma I. MIXED session, Tuesday morning, October 20 South Pacific Ballroom, Aston Wailea," (http://www.aps.org/BAPSGEC98/abs/S2000.html) (October 22, 2001) pp.1-4

EXAMINER <i>Kenneth J. Wood</i>	DATE CONSIDERED <i>5/13/03</i>
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